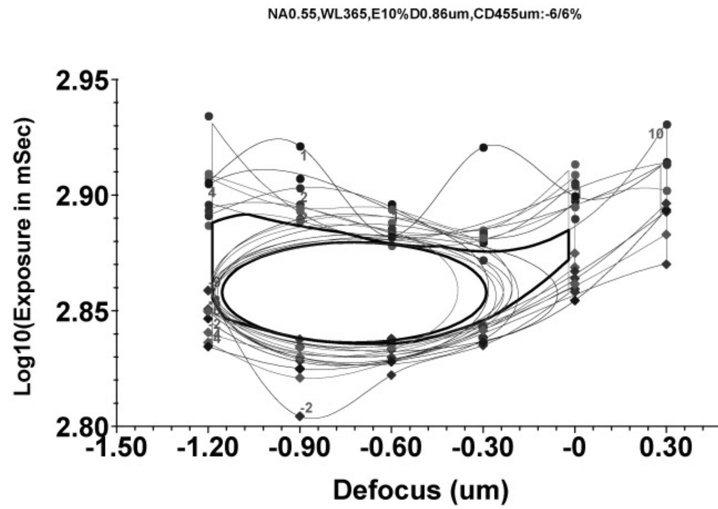
Errata for *Optical Lithography: Here Is Why* **April 5, 2011**

1. Page 96, Eq. 4.1:

$$W = k_1 \cdot \frac{\lambda}{NA}$$

2. Page 126, Fig. 4.40:



3. Page 127, Fig. 4.41:

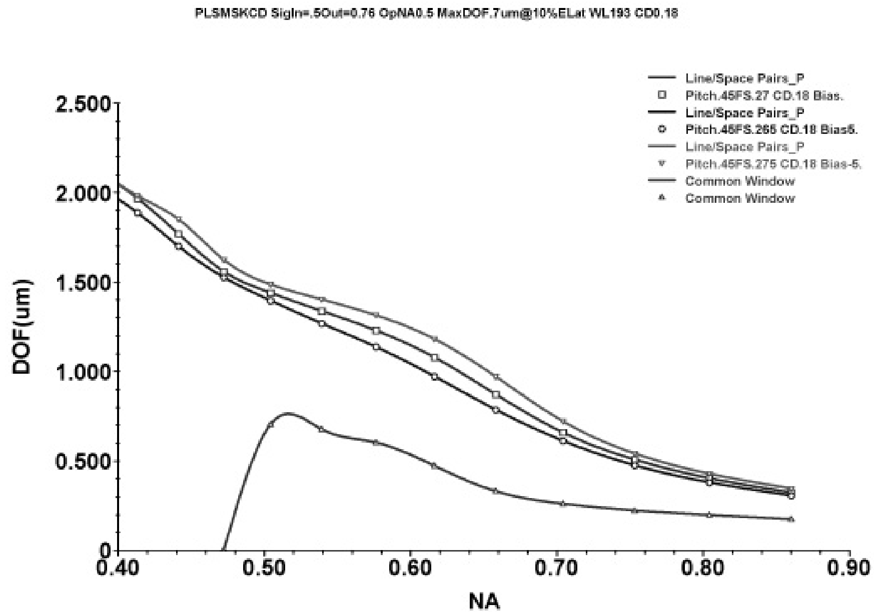
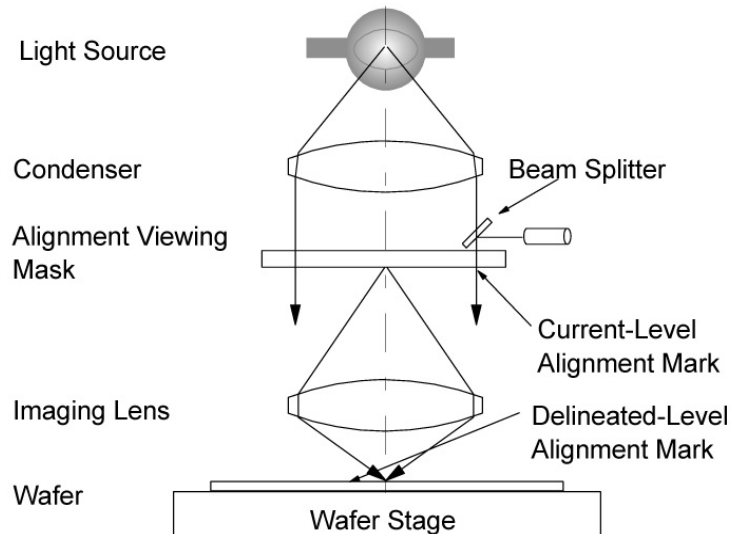


Figure 4.41 DOF versus NA from E-D trees with 0- and ±5-nm mask biases.

4. Pages 128 through 130, captions for Figs. 4.42 through 4.46:
   Replace "E-D trees from" with "DOF versus NA from E-D trees with"

5. Page 205, Fig. 5.71:



6. Page 208, References 1 and 2:

1 K. Jain, C. G. Willson, and B. J. Lin, "Ultrafast deep-UV lithography with excimer lasers," *IEEE Electron. Dev. Lett.* **EDL-3**, p. 53 (1983).

2 K. Jain and C. G. Willson, "Ultrafast deep UV lithography with excimer lasers," *Appl. Phys. B* **28**, p. 206 (1982).

7. Page 282, Fig. 6.79 caption:

   Figure 6.79 Ripples in the resist image in unoptimized OPC conditions.

8. Page 283, Fig. 6.80 caption:

   Figure 6.80 Diffracted image from the BigMaC BIM with RGI.